

Synthesis of Carbon Nanotubes over Electroless-Plating Ni Films and Their Applications as the Electrode Materials of Ele

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ABSTRACT

In this study, multi-walled carbon nanotubes were synthesis by thermal chemical vapor deposition over electroless plating nickel films with silicon substrate as the sbustrate. For the application of the electrochemical capacitors, carbon nanotubes were directly grown on the glassy carbon electrode with/without the electrodeposited ruthenium oxides onto the surface of the as-deposited carbon nanotubes films. The electrochemical behaviors of the as-prepared carbon electrodes were investigated by cyclic voltammetry. The results showed that: (a). Before electroless nickel plating, a process to sensitize and activated the substrate is necessary to achieve uniform and highly dispersive Ni films in a shorter duration, (b). The thinner and uniformly coated Ni-P particles, the smaller the diameters of the multi-walled carbon nanotubes are grown with more denser nanotubes distribution, (c). Hydrogen is necessary for CNT growth to prevent other amorphous carbonaceous carbon depoited. (d). NH₃ ambient is helpful for better control of the nanotubes structure and growth density both in pretreatment and growth stage. (e). Cyclic voltammograms shows that the pseudocapacitive behavior of as-grown multiwalled carbon nanotubes functionctionalized with electrodeposited Ruthenium oxides. The specific capacitance of the CNTs and Ruthenium oxides functionalized CNTs is apparently greater than that of pristine GCE in the same medium.

Keywords : Electroless Plating ; Thermal CVD ; Multi-walled Carbon nanotube (MWNT) ; glassy carbon electrode(GCE) ; ruthenium oxide ; pseudocapacitive

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